IFW

DOCKET NO.: 278426US0PCT

IN THE UNITED STATES AND TRADEMARK OFFICE

AUG 1 4 2006

IN RE APPLICATION OF:

GROUP: 3723

Mitsugu ABE, et al.

SERIAL NO: 10/549,294

ATTENTION:

FILING RECEIPT CORRECTIONS

FILED:

September 16, 2005

FOR:

MATERIAL FOR PURIFICATION OF SEMICONDUCTOR POLISHING

SLURRY, MODULE FOR PURIFICATION OF SEMICONDUCTOR

POLISHING SLURRY AND PROCESS FOR PRODUCING

SEMICONDUCTOR POLISHING SLURRY

2ND REQUEST FOR CORRECTED OFFICIAL FILING RECEIPT

Office of Initial Patent Examination Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

The Patent Office is requested to provide a corrected Official Filing Receipt for the following.

PLEASE NOTE THAT THE 4TH APPLICANT'S CITY IS INCORRECT. IT SHOULD READ AS FOLLOWS:

- 1) MITSUGU ABE, ATSUGI-SHI, JAPAN;
- 2) NOBUYOSHI NAMBU, YOKKAICHI-SHI, JAPAN;
- 3) OSAMU ITO, YOKKAICHI-SHI, JAPAN;
- 4) MASAAKI OGITSU, <u>TSUKUBA-SHI</u>, JAPAN;
- 5) KAZUO INOMATA, TOKYO, JAPAN.

No fees are required. If you have any questions, please do not hesitate to contact us.

Respectfully Submitted,

James H. Knebel

Registration No. 22,630

OBLON, SPIVAK, McCLELLAND, MAIER & NEUSTADT, P.C. Norman F. Oblon

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DOCKET NO.: 278426US-3069-4314-0PCT

APPLICATION SERIAL NO.: 10/549,294



UNITED STATES DEPARTMENT OF COMMERCE United States Patent and Trademark Office Address: COMMISSIONER FOR PATENTS P.O. Box 1430 Alexandria, Virginia 22313-1450 www.uspto.gov

APPL NO.	FILING OR 371 (c) DATE	ART UNIT	FIL FEE REC'D	ATTY.DOCKET NO	DRAWINGS	TOT CLMS	IND CLMS
10/549,294	09/16/2005	3723	1260	278426US0PCT	6	14	2

CONFIRMATION NO. 8085

REPLACEMENT FILING RECEIPT

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22850 C. IRVIN MCCLELLAND OBLON, SPIVAK, MCCLELLAND, MAIER & NEUSTADT, P.C. 1940 DUKE STREET ALEXANDRIA, VA 22314

Date Mailed: 07/31/2006

Receipt is acknowledged of this regular Patent Application. It will be considered in its order and you will be notified as to the results of the examination. Be sure to provide the U.S. APPLICATION NUMBER, FILING DATE, NAME OF APPLICANT, and TITLE OF INVENTION when inquiring about this application. Fees transmitted by check or draft are subject to collection. Please verify the accuracy of the data presented on this receipt. If an error is noted on this Filing Receipt, please mail to the Commissioner for Patents P.O. Box 1450 Alexandria Va 22313-1450. Please provide a copy of this Filing Receipt with the changes noted thereon. If you received a "Notice to File Missing Parts" for this application, please submit any corrections to this Filing Receipt with your reply to the Notice. When the USPTO processes the reply to the Notice, the USPTO will generate another Filing Receipt incorporating the requested corrections (if appropriate).

Applicant(s)

Mitsugu Abe, Atsugi-shi, JAPAN; Nobuyoshi Nambu, Yokkaichi-shi, JAPAN; Osamu Ito, Yokkaichi-shi, JAPAN; Masaaki Ogitsu, Tsukuba, JAPAN; Kazuo Inomata, Tokyo, JAPAN; TSUKUBA SHI

Assignment For Published Patent Application

Nomura Micro Science Co., Ltd., Atsugi-shi, Kanagawa, JAPAN

MAIER & NEUSTADT, P.C.

DOCKETING DEPT

Initials/Date Docketed:
Type of Resp(s):

OBLON, SPIVAK, McCLELLAND

RECEIVED:

Due Date(s):

Power of Attorney: The patent practitioners associated with Customer Number <u>22850</u>.

Domestic Priority data as claimed by applicant

This application is a 371 of PCT/JP04/03642 03/18/2004

Foreign Applications

JAPAN 2003-074581 03/18/2003

If Required, Foreign Filing License Granted: 06/04/2006

The country code and number of your priority application, to be used for filing abroad under the Paris Convention, is US10/549,294.

Projected Publication Date: 09/14/2006

Non-Publication Request: No

Early Publication Request: No

Title

Material for purification of semiconductor polishing slurry, module for purification of semiconductor polishing slurry and process for producing semiconductor polishing slurry

Preliminary Class

451

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